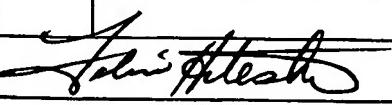


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Sheet 1 of 1

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|---|----------|---|--|--|---|
|   |          |   | <b>APPLICANTS</b><br>Izumi FUSEGAWA et al. |  |   |
|   |          |   | <b>FILING DATE</b><br>February 13, 2006    |  |   |
| <b>U.S. PATENT DOCUMENTS</b>  |          |   |  |  |   |
| Examiner Initials   | Cite No. | Document Number   | Date                                       | Name   |   |
| F.H.  | 1.       | 2003/0116082 A1   | 06/26/2003                                 | Masahiro SAKURADA et al.   |   |
| F.H.  | 2.       | 2002/0157600 A1   | 10/31/2002                                 | Izumi FUSEGAWA et al.  |   |
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| F.H.  | 3.       | JP-A-2002-201093  | 07/16/2002                                 | JAPAN  | X      X  |
| A   | 4.       | WO 01/63027 A1  | 08/30/2001                                 | WIPO   | X   |
|   | 5.       | WO 01/81661 A1  | 11/01/2001                                 | WIPO   | X   |
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|   | 7.       | JP-A-07-041383  | 02/10/1995                                 | JAPAN  | X      X  |
| V   | 8.       | JP-A-08-330316  | 12/13/1996                                 | JAPAN  | X      X  |
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| F.H.  | 11.      | Makoto TAKIYAMA et al.; "Dielectric Degradation of Silicon Dioxide Films Cased by Metal Contaminations"; <i>Ultra Clean Technology</i> ; Vol. 5, No. 5/6; Nippon Steel Corporation; pp. 345-359. (with abstract) <i>Year 2000</i> |  |  |   |
|   |          |   |  |  |   |
|   |          |   |  |  |   |
|   |          |   |  |  |   |
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